IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

n re Application of:)
YASUHISA INAO, ET AL.	j
Application No.: 10/663,691	j
Filed: September 17, 2003)
For: MASK, EXPOSURE APPARATUS, AND EXPOSURE METHOD	:) : December 18, 2003

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

Sir:

In compliance with the duty of disclosure under 37 C.F.R. § 1.56 and in accordance with the practice under 37 C.F.R. §§ 1.97 and 1.98, the Examiner's attention is directed to the documents listed below and on the enclosed Form PTO-1449. Copies of documents (2) and (3) are also enclosed, along with an English-language abstract for document (2).

- (1) U.S. Patent No. 6,171,739
- (2) Japan 2000-112116
- (3) "Sub-diffraction-limited patterning using evanescent near-field optical lithography," M.M. Alkaisi et al., Applied Physics Letters (1999), Vol. 75, No. 22, pp. 3560-3562.

These documents were cited on page 8 of the subject application, and might

be deemed relevant for the reasons noted therein.

A copy of the newly cited U.S. Patent Application is not being provided in

accordance to the Pre-Official Gazette Notice dated, July 11, 2003, entitled "Information

Disclosure Statements Filed Without Copies Of U.S. Patents and Published Applications in

Patent Applications filed after June 30, 2003.

Inasmuch as the subject application has not yet received a first Office

Action, it is believed that this Information Disclosure Statement is timely. See 37 C.F.R.

1.97(b)(3). Accordingly, the Examiner is urged to study this information in its entirety and

to form an independent determination of the materiality of the information to the claimed

invention. Additionally, the Examiner is requested to indicate that this information has

been considered by initialing the appropriate portion of the Form PTO-1449.

Applicants' undersigned attorney may be reached in our Costa Mesa,

California office by telephone at (714) 540-8700. All correspondence should continue to

be directed to our address given below.

Respectfully submitted,

Attorney for Applicants/

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FORM PTO 1449 (modified)		ATTY DOCKET NO. 00684.003542.	APPLICATION NO. 10/663,691				
U.S. DEPARTMENT OF COMMERCE PE		APPLICANT YASUHISA INAO, ET AL.					
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*EXAMINER INITIAL	DOCUMENT NUMBER	DATE DATE	NAME	CLASS	SUBCLASS	FILING DATE	
·	6,171,739	01/09/01	Spence et al.	430	30		
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		FOR	REIGN PATENT DOCUMENTS	1			
	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES/NO/ OR ABSTRACT	
	2000-112116	04/21/00	Japan			Abstract	
	וס	HER DOCUMENT(S)	(Including Author, Title, Date, Pertinent Pages, Etc.)				
"Sub-diffraction-limited patterning using evanescent near-field optical lithography," M.M. Alkaisi et al., Applied Physics Letters (1999), Vol. 75, No. 22, pp. 3560-3562.							
EXAMINER DATE CONSIDERED							

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^{*}EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.